

ABSTRACT

A sheetfed resist removing apparatus having a substrate (111) being a cleaning object placed therein, includes a treatment chamber (101) forming a closed space, and a spray nozzle (102) to spray a cleaning liquid in a form so-called liquid drops over a surface of the substrate (111), in which the treatment chamber (101) forms the closed space containing the substrate (111) such that the placed substrate (111) faces the spray nozzle (102). This structure allows a cleaning liquid to be in the form of liquid drops in consideration of energy reduction, and permits desirable regulation of the temperature of the liquid drops when the liquid drops contact with the resist film in spraying the cleaning liquid over the resist film on the surface of the substrate (111) to thereby remove the resist film, so that secure removal of the resist film can be accomplished.